L Number	Hits	Search Text	DB	Time stamp
3	238	(((((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/16 17:33
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		
		(hydrogen "H.sub.2")) (((((((silicon		
		(amorphous near3 silicon) a-silicon a-si)) and (air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
		(anneal\$3 heat\$3)) and crystal\$10) and (HF		
		(hydrogen near3 fluoride) (hydrofluor\$3		į
		near3 acid))) and (oxygen "O.sub.2"))		
		((((((((silicon (amorphous near3 silicon)		
		a-silicon a-si) ) and (air ambient		
		atmosphere)) and ((native natural) near5	}	
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		
		(nitrogen "N.sub.2"))) and (TFT (thin near3		
5	E 2	<pre>film near3 transistor)) ((laser same ((natural near3 oxide)</pre>	IICDATE:	2004/06/16 12 26
,	53	native))) and (TFT (thin near3 film near3	USPAT; US-PGPUB	2004/06/16 13:26
		transistor))	US-FGFUB	
4	885	(laser same ((natural near3 oxide) native))	USPAT:	2004/06/16 17:11
			US-PGPUB	
6	126	(laser same ((natural near3 oxide) native))	EPO; JPO;	2004/06/16 17:11
			DERWENT;	
			IBM_TDB	
7	183	(laser and ((natural near3 oxide) native))	EPO; JPO;	2004/06/16 17:11
			DERWENT;	
8	183	//lagon and //national massa sociation and the	IBM_TDB	2004/05/25 5= 5
	163	((laser and ((natural near3 oxide) native))) ((laser same ((natural near3 oxide)	EPO; JPO;	2004/06/16 17:12
		native)))	DERWENT; IBM TDB	
9	9	(((laser and ((natural near3 oxide)	EPO; JPO;	2004/06/16 17:12
		native))) ((laser same ((natural near3	DERWENT;	-301,00,10 17.12
		oxide) native)))) and (TFT (thin near3 film	IBM TDB	
		near3 transistor))	_	
10	0	(((((((((silicon (amorphous near3 silicon)	EPO; JPO;	2004/06/16 17:33
	1	a-silicon a-si) ) and (air ambient	DERWENT;	
		atmosphere)) and ((native natural) near5	IBM_TDB	
		oxid\$6)) and laser) and (anneal\$3 heat\$3)) and crystal\$10) and (HF (hydrogen near3		
	i	fluoride) (hydrofluor\$3 near3 acid))) and		
		(hydrogen "H.sub.2")) (((((((silicon		
		(amorphous near3 silicon) a-silicon a-si) )		
		and (air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
-		(anneal\$3 heat\$3)) and crystal\$10) and (HF		
		(hydrogen near3 fluoride) (hydrofluor\$3		
		near3 acid))) and (oxygen "O.sub.2"))		
		(((((((((silicon (amorphous near3 silicon)		
ļ		a-silicon a-si) ) and (air ambient atmosphere)) and ((native natural) near5		
	i	oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		
		(nitrogen "N.sub.2"))) and (TFT (thin near3		
		film near3 transistor))		
-	425153	(silicon (amorphous near3 silicon) a-silicon	USPAT;	2004/06/03 21:33
	0.000.0	a-si)	US-PGPUB	
-	219940	((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:35
		a-silicon a-si) ) and (air ambient	US-PGPUB	
_	6996	atmosphere) (((silicon (amorphous near3 silicon)	IICDAM.	2004/05/02 05 05
	0990	a-silicon a-si) ) and (air ambient	USPAT; US-PGPUB	2004/06/03 21:35
		atmosphere)) and ((native natural) near5	JO FGFUB	
		oxid\$6)		
			<del></del>	

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-	1886		USPAT;	2004/06/03 21:35
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5	1	
		oxid\$6)) and laser		
_	1751	(((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:19
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5	05 10102	,
		oxid\$6)) and laser) and (anneal\$3 heat\$3)		
	1393		,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	2004/06/02 21 25
_	1393	((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:35
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5		1
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10	-	
-	572	((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:35
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride))	1	
	707			
] -	787	( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( ( (	USPAT;	2004/06/03 21:25
		a-silicon a-si) ) and (air ambient	US-PGPUB	
	1	atmosphere)) and ((native natural) near5		
1		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
1		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))		
_	620	(((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:36
		a-silicon a-si) ) and (air ambient	US-PGPUB	2004,00,03 21:30
		atmosphere)) and ((native natural) near5	05 FGF0B	1
			†	
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
1		and crystal\$10) and (HF (hydrogen near3		1
İ		fluoride) (hydrofluor\$3 near3 acid))) and		
		(hydrogen "H.sub.2")		İ
-	706	(((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:36
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
	1	fluoride) (hydrofluor\$3 near3 acid))) and		
		(oxygen "O.sub.2")		
_	598		USPAT:	2004/06/02 21 26
		a-silicon a-si) ) and (air ambient		2004/06/03 21:36
			US-PGPUB	i
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
1	1	and crystal\$10) and (HF (hydrogen near3		
	1	fluoride) (hydrofluor\$3 near3 acid))) and		
		(nitrogen "N.sub.2")		
-	768	((((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:27
	1	a-silicon a-si) ) and (air ambient	US-PGPUB	, ,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,
		atmosphere)) and ((native natural) near5		]
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
	1			
		fluoride) (hydrofluor\$3 near3 acid))) and		
]		(hydrogen "H.sub.2")) (((((((silicon		
1		(amorphous near3 silicon) a-silicon a-si) )		
		and (air ambient atmosphere)) and ((native		
1		natural) near5 oxid\$6)) and laser) and		
1		(anneal\$3 heat\$3)) and crystal\$10) and (HF		`
[		(hydrogen near3 fluoride) (hydrofluor\$3		
1		near3 acid))) and (oxygen "O.sub.2"))		
1		(((((((silicon (amorphous near3 silicon)		]
1		a-silicon a-si) ) and (air ambient		
			i	
I		atmognhere)) and ((native natural) name		l l
ĺ		atmosphere)) and ((native natural) near5		
	ļ	oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		<pre>oxid\$6)) and laser) and (anneal\$3 heat\$3)) and crystal\$10) and (HF (hydrogen near3</pre>		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		

-	235	(((((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/16 13:14
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
0		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		
		(hydrogen "H.sub.2")) (((((((silicon		
		(amorphous near3 silicon) a-silicon a-si) )		
		and (air ambient atmosphere)) and ((native		1
		natural) near5 oxid\$6)) and laser) and	ļ	
		(anneal\$3 heat\$3)) and crystal\$10) and (HF		i
		(hydrogen near3 fluoride) (hydrofluor\$3		
		near3 acid))) and (oxygen "O.sub.2"))		
		((((((((silicon (amorphous near3 silicon)		
		a-silicon a-si) ) and (air ambient		
		atmosphere)) and ((native natural) near5		
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		
	1	(nitrogen "N.sub.2"))) and (TFT (thin near3 film near3 transistor))		
_	425229		LICDAM	2004/06/02 03 24
_	423229	(silicon (amorphous near3 silicon) a-silicon a-si alpha-silicon alpha-Si)	USPAT;	2004/06/03 21:34
I _	219971		US-PGPUB	2004/05/02 01 25
	2199/1	((silicon (amorphous near3 silicon)   a-silicon a-si alpha-silicon alpha-Si) ) and	USPAT; US-PGPUB	2004/06/03 21:35
		(air ambient atmosphere)	US-PGPUB	
_	6996		IIODATI.	2004/06/02 21 25
	0330	a-silicon a-si alpha-silicon alpha-Si) ) and	USPAT; US-PGPUB	2004/06/03 21:35
		(air ambient atmosphere)) and ((native	03-FGF0B	
		natural) near5 oxid\$6)		
_	1886	((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:35
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	2004/00/03 21:33
	1	(air ambient atmosphere)) and ((native	05 10105	
		natural) near5 oxid\$6)) and laser		
-	1460	((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:35
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	2001,00,03 21.33
		(air ambient atmosphere)) and ((native	33 13132	
		natural) near5 oxid\$6)) and laser) and		
		crystal\$10		
-	587	((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:36
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
		crystal\$10) and (HF (hydrogen near3		
		fluoride))		
-	446	''''   '''   ''''   '''''''   ''''''''	USPAT;	2004/06/03 21:36
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
1		crystal\$10) and (HF (hydrogen near3		
1		fluoride))) and (hydrogen "H.sub.2")		
-	524	· · · · · · · · · · · · · · · · · · ·	USPAT;	2004/06/03 21:36
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
:		crystal\$10) and (HF (hydrogen near3		
[_	20-	fluoride))) and (oxygen "O.sub.2")		
<u> </u>	381	(((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:37
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	
		(air ambient atmosphere)) and ((native		
ļ		natural) near5 oxid\$6)) and laser) and		
		crystal\$10) and (HF (hydrogen near3		
		fluoride))) and (oxygen "O.sub.2")) and		
L	<u> </u>	(nitrogen "N.sub.2")		

-	564	(((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:37
		a-silicon a-si alpha-silicon alpha-Si) ) and	US-PGPUB	
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
	1	crystal\$10) and (HF (hydrogen near3		
		fluoride))) and (hydrogen "H.sub.2"))		
		(((((((silicon (amorphous near3 silicon)	1	
		a-silicon a-si alpha-silicon alpha-Si) ) and		
		(air ambient atmosphere)) and ((native	Ì	
		natural) near5 oxid\$6)) and laser) and		
		crystal\$10) and (HF (hydrogen near3		
		fluoride))) and (oxygen "O.sub.2"))		
		((((((((silicon (amorphous near3 silicon)		
		a-silicon a-si alpha-silicon alpha-Si) ) and	]	
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
		crystal\$10) and (HF (hydrogen near3		
		fluoride))) and (oxygen "O.sub.2")) and		
		(nitrogen "N.sub.2"))		
-	780	(((((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:38
		a-silicon a-si) ) and (air ambient	US-PGPUB	
		atmosphere)) and ((native natural) near5	}	
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		ł
		(hydrogen "H.sub.2")) (((((((silicon	]	
		(amorphous near3 silicon) a-silicon a-si) )	Ì	
	1	and (air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
		(anneal\$3 heat\$3)) and crystal\$10) and (HF		
		(hydrogen near3 fluoride) (hydrofluor\$3		
				]
		near3 acid))) and (oxygen "O.sub.2"))		
		((((((((silicon (amorphous near3 silicon)		
	•	a-silicon a-si) ) and (air ambient		Į.
		atmosphere)) and ((native natural) near5		1
		oxid\$6)) and laser) and (anneal\$3 heat\$3))		
		and crystal\$10) and (HF (hydrogen near3		
		fluoride) (hydrofluor\$3 near3 acid))) and		l i
		(nitrogen "N.sub.2"))) (((((((silicon		
		(amorphous near3 silicon) a-silicon a-si		
	1	alpha-silicon alpha-Si) ) and (air ambient		
		atmosphere)) and ((native natural) near5		ļ
		oxid\$6)) and laser) and crystal\$10) and (HF		1
		(hydrogen near3 fluoride))) and (hydrogen		
		"H.sub.2")) (((((((silicon (amorphous near3		
		silicon) a-silicon a-si alpha-silicon		
		alpha-Si) ) and (air ambient atmosphere))		
		and ((native natural) near5 oxid\$6)) and		
		laser) and crystal\$10) and (HF (hydrogen		
		near3 fluoride))) and (oxygen "O.sub.2"))		
		((((((((silicon (amorphous near3 silicon)		
	ļ	a-silicon a-si alpha-silicon alpha-Si) ) and		
		(air ambient atmosphere)) and ((native		
		natural) near5 oxid\$6)) and laser) and		
		crystal\$10) and (HF (hydrogen near3		
		fluoride))) and (oxygen "O.sub.2")) and		
		(nitrogen "N.sub.2")))		
	L	(mrerogen "N.sub.2")))		

		T	
- 235	((((((((((silicon (amorphous near3 silicon)	USPAT;	2004/06/03 21:38
	a-silicon a-si) ) and (air ambient	US-PGPUB	
	atmosphere)) and ((native natural) near5		1
	oxid\$6)) and laser) and (anneal\$3 heat\$3))		
	and crystal\$10) and (HF (hydrogen near3		
	fluoride) (hydrofluor\$3 near3 acid))) and		
	(hydrogen "H.sub.2")) (((((((silicon		
i	(amorphous near3 silicon) a-silicon a-si) )		
	and (air ambient atmosphere)) and ((native		
1	natural) near5 oxid\$6)) and laser) and		
	(anneal\$3 heat\$3)) and crystal\$10) and (HF	ĺ	!
ļ	(hydrogen near3 fluoride) (hydrofluor\$3		Ī
	near3 acid))) and (oxygen "O.sub.2"))		
	((((((((silicon (amorphous near3 silicon)		
	a-silicon a-si) ) and (air ambient		
	atmosphere)) and ((native natural) near5		
	oxid\$6)) and laser) and (anneal\$3 heat\$3))		
	and crystal\$10) and (HF (hydrogen near3		
į.	fluoride) (hydrofluor\$3 near3 acid))) and		
	(nitrogen "N.sub.2"))) ((((((((silicon		
	(amorphous near3 silicon) a-silicon a-si		
	alpha-silicon alpha-Si) ) and (air ambient		
	atmosphere)) and ((native natural) near5		
	oxid\$6)) and laser) and crystal\$10) and (HF		
	(hydrogen near3 fluoride))) and (hydrogen		
1	"H.sub.2")) (((((((silicon (amorphous near3		
	silicon) a-silicon a-si alpha-silicon		
	alpha-Si) ) and (air ambient atmosphere))		
	and ((native natural) near5 oxid\$6)) and		
	laser) and crystal\$10) and (HF (hydrogen		
	near3 fluoride))) and (oxygen "O.sub.2"))		
	((((((((silicon (amorphous near3 silicon)		
	a-silicon a-si alpha-silicon alpha-Si) ) and		
	(air ambient atmosphere)) and ((native		
	natural) near5 oxid\$6)) and laser) and		
	crystal\$10) and (HF (hydrogen near3		
	fluoride))) and (oxygen "O.sub.2")) and		
	(nitrogen "N.sub.2")))) and (TFT (thin near3		
	<pre>film near3 transistor))</pre>		